Temperature-induced Valley Polarization in WS₂ Heterostructures

Davoud Adinehloo¹, Ioannis Paradisanos^{2,3}, Kathleen M. McCreary⁴, Leonidas Mouchliadis², Jeremy T. Robinson⁵, Hsun-Jen Chuang⁴, Aubrey T. Hanbicki⁴, Berend T. Jonker⁴, Emmanuel Stratakis^{2,6}, George Kioseoglou² and Vasili Perebeinos¹



Motivation

We investigate the temperature dependence of valley polarization in WS₂ heterostructures. The influence of heterostructures of different materials on the degree of valley polarization is depicted. The intervalley scattering rates under resonant and non-resonant excitation energy as the crucial parameters to see the temperature dependence by considering Fröhlich coupling are calculated. The results show the scattering rate is almost independent of temperature due to a large phonon energy. Subsequently, the major contribution of the observed valley depolarization should come from the change in the radiative lifetime.

The scattering rate is calculated using Fermi Golden's rule:

$$\frac{1}{\tau_k} = \frac{2\pi}{\hbar} \sum_{k'} |\Gamma(q)|^2 \begin{bmatrix} N(T)\delta(\varepsilon_{k'} - \varepsilon_k - \hbar\omega) + \\ (1 + N(T))\delta(\varepsilon_{k'} - \varepsilon_k + \hbar\omega) \end{bmatrix}$$

 Table 1 - Energies and dielectric constants of used materials.

To measure the polarization, the system is excited with right-handed circularly polarized light (σ +), and then the resultant photoluminescence is analysed for copolarized (σ +) and cross-polarized/left-handed circularly polarized light (σ -). The degree of valley polarization is related to the circularly polarized emission (P_{circ})1,2 where $P_{circ} = (I_+ - I_-)/(I_+ + I_-)$, and $I_+ (I_-)$ is the intensity of the σ + (σ -) helicity PL component. In Figs. 2a and 2b, the X⁰ temperature-dependent polarization degree of hBN/WS₂/hBN and WS2/Gr are shown for non- and near-resonant excitation conditions using the 543nm (2.283eV) and 594nm (2.087eV) laser sources, respectively. Figs. 2c and 2d show scattering rate from the bottom of the conduction band at the K point to all available states near the K' point. The bandgap energy shift due to electronphonon coupling is shown in Fig. 3b, where the temperature dependence of the bandgap shift is much weaker than observed in the experiment (Fig. 3a).

Structure

A schematic structure of the heterostuctures is depicted in Fig. 1. Atomically thin materials 1 and 2 are bounded between two semi-infinite substrate materials 3 and 4, characterized by their dielectric functions.

	$\hbar\omega_{TO}[meV]$	$\hbar\omega_{LO}[meV]$	$\varepsilon(0)$	$\varepsilon(\infty)$
WS_2	42.9	43	13.7	13.6
hBN	97.6	103	5.1	4.58
SiO ₂	55.7	60	3.9	3.36

Results

The results of the measurements and theoretical calculations are shown below².







Figure 1: Schematic structure of heterostrutures.

Theory

To find the Fröhlich coupling, we solve Maxwell equations in the form of¹

$$\begin{split} \phi(\boldsymbol{\rho}, z) &= \sum_{q} \phi(q, z) e^{iq.\boldsymbol{\rho}}, \\ \phi(q, z) &= \phi_0 \begin{cases} (\alpha_1 + 1)e^{-qz} & z \leq t_1 \\ \alpha_1 e^{q(z-2t_1)} + e^{-qz} & 0 < z \leq t_1 \\ (1 + \alpha_1 e^{-2qt_1}) [(1 - \alpha_2 e^{-qt_2})e^{qz} + \alpha_2 e^{-q(z+t_2)}] & -t_2 < z \leq 0, \\ (\alpha_2(1 - e^{-2qt_2}) + e^{-qt_2})(1 + \alpha_1 e^{-2qt_1})e^{q(z+t_2)} & z \leq -t_2 \end{cases} \end{split}$$

Figure 3: Temperature dependent energy shift of X^0 in hBN / WS₂ / hBN and WS₂ / Gr. (a) Experimental and (b) theory. In (a) the energy shift is normalized and set to 0 at 4K in both cases.

Conclusion

We have demonstrated temperature dependent valley polarization measurements in CVD-grown a) monolayer WS₂ encapsulated in hBN and b)

$$\alpha_1 = \frac{\epsilon_1 - \epsilon_4}{\epsilon_1 + \epsilon_4}, \qquad \alpha_2 = \frac{(\epsilon_2 - \epsilon_3)\exp(-qt_2)}{\epsilon_2 + \epsilon_3 + (\epsilon_2 - \epsilon_3)\exp(-2qt_2)},$$

The frequencies can be obtained by the secular equation and ϕ_0 is related to the energy of excitation quanta $\hbar \omega_q$.

The Hamiltonain can be written as

 $H = \sum_{q} -e\phi(q,z)e^{iq}\left(a_{q} + a_{-q}^{\dagger}\right),$

 $E_k=200 \text{meV}$ 10 100 150 200 250300 50 Temperature (K)

Figure 2: Temperature dependent valley polarization degree for a neutral exciton (X^0) in hBN / WS₂ / hBN and WS₂ / Gr hetrostructures as a function of temperature under (a) 543nm and (b) 594nm excitations. The intervalley scattering rates in WS₂ heterostructures. (c) ϵ_k =55meV (near-resonant), and (d) ϵ_k =200meV (offresonant). monolayer WS_2 on top of graphene excited by two different photon energies. The electron-phonon model partly explains for the observed temperature dependency.

References

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¹ Department of Electrical Engineering, University at Buffalo, The State University of New York, Buffalo, NY 14260, USA ² Institute of Electronic Structure and Laser, Foundation for Research and Technology - Hellas, Heraklion, 71110, Crete, Greece

³ Department of Physics, University of Crete, Heraklion, 71003, Crete, Greece

⁴ Materials Science and Technology Division, Naval Research Laboratory, Washington, DC 20375, USA
 ⁵ Electronics Science and Technology Division, Naval Research Laboratory, Washington, DC 20375, USA
 ⁶ Department of Materials Science and Technology, University of Crete, Heraklion, 71003 Crete, Greece davoudad@buffalo.edu